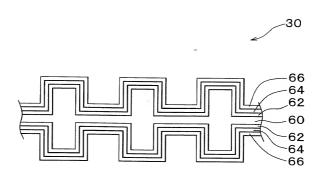
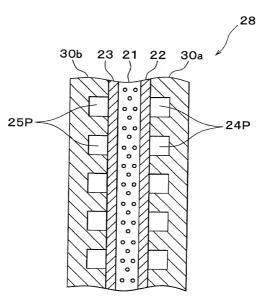
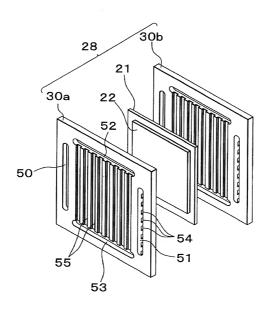
FIG. 1

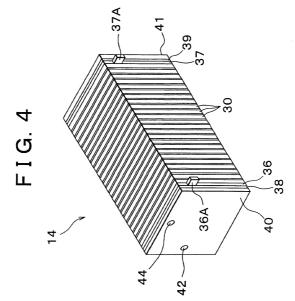


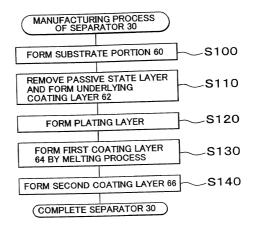
F I G. 2



F I G. 3







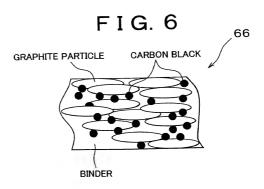


FIG. 7A

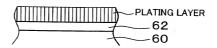
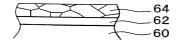


FIG. 7B



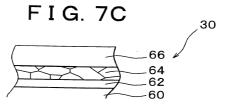
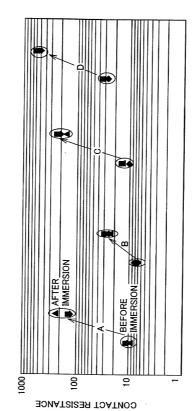


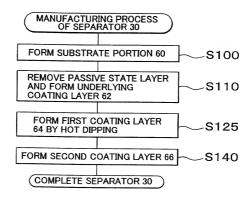
FIG. 8

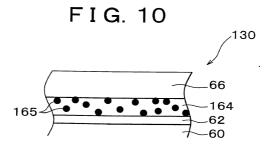


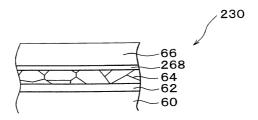
A: Sn-Bi, WITHOUT MELTING PROCESS

- B: Sn-Bi、WITH MELTING PROCESS (AIR-COOLING)
- C: Sn-Bi, WITH MELTING PROCESS (WATER-COOLING)
 - D:Sn, WITH MELTING PROCESS (AIR-COOLING)

FIG. 9

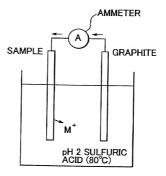






SURFACE TREATMENT	CORROSION CURRENT*1 (µ A/cm²)	CONTACT RESISTANCE *2 (mΩcm³)
E:0.1 μ mAg/10 μ mCu	6.9	10 OR LESS
F:0.1 μ mAg/10 μ mSn(UNPROCESSED) /10 μ mCu	21.9	10 OR LESS
G:0.1 μ mAg/10 μ mSn(MELTING PROCESS) /10 μ mCu	0.3	10 OR LESS

- * 1: RESULT OBTAINED WITHOUT CARBON COATING LAYER OF CARBON MATERIALS
- * 2: RESULT OBTAINED WITH CARBON COATING LAYER OF CARBON MATERIALS



CARBON CORTING LAYER*	PRESENT
CORROSION -RESISTANT COATING LAYER*	PRESENT
CONDUCTIVE PARTICLES*	PRESENT
METAL COATING LAYER*	METAL HAVING LOWER MELTING POINT THAN MATERIAL OF SEPARATOR BASE MATERIAL AND HAVING BEN SUBJECTED TO MELTING PROCESS OR METAL HAVING CRYSTAL GRAIN SIZE OF 0.1 mm OR MORE
PREDETER MINED PROCESS*	PRESENT
SEPARATOR PREDETER BASE MINED PROCESS*	PRESENT

*: ANY MATERIAL AS DESCRIBED IN THE SPECIFICATION CAN BE SELECTED AS APPROPRIATE